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Sugiura et al.

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(54) **CEILING HEATER FOR SUBSTRATE
PROCESSING APPARATUS**

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(30) **Foreign Application Priority Data**

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(52) **U.S. Cl.**
USPC **D13/182**

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D15/146, 140; D23/314, 322, 333, 415,
D23/417, 499
CPC H01L 21/67115; H01L 21/67098; H01L
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See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a ceiling heater for substrate
processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front, top and right side perspective view of a
ceiling heater for substrate processing apparatus showing
our new design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a left side elevational view thereof;

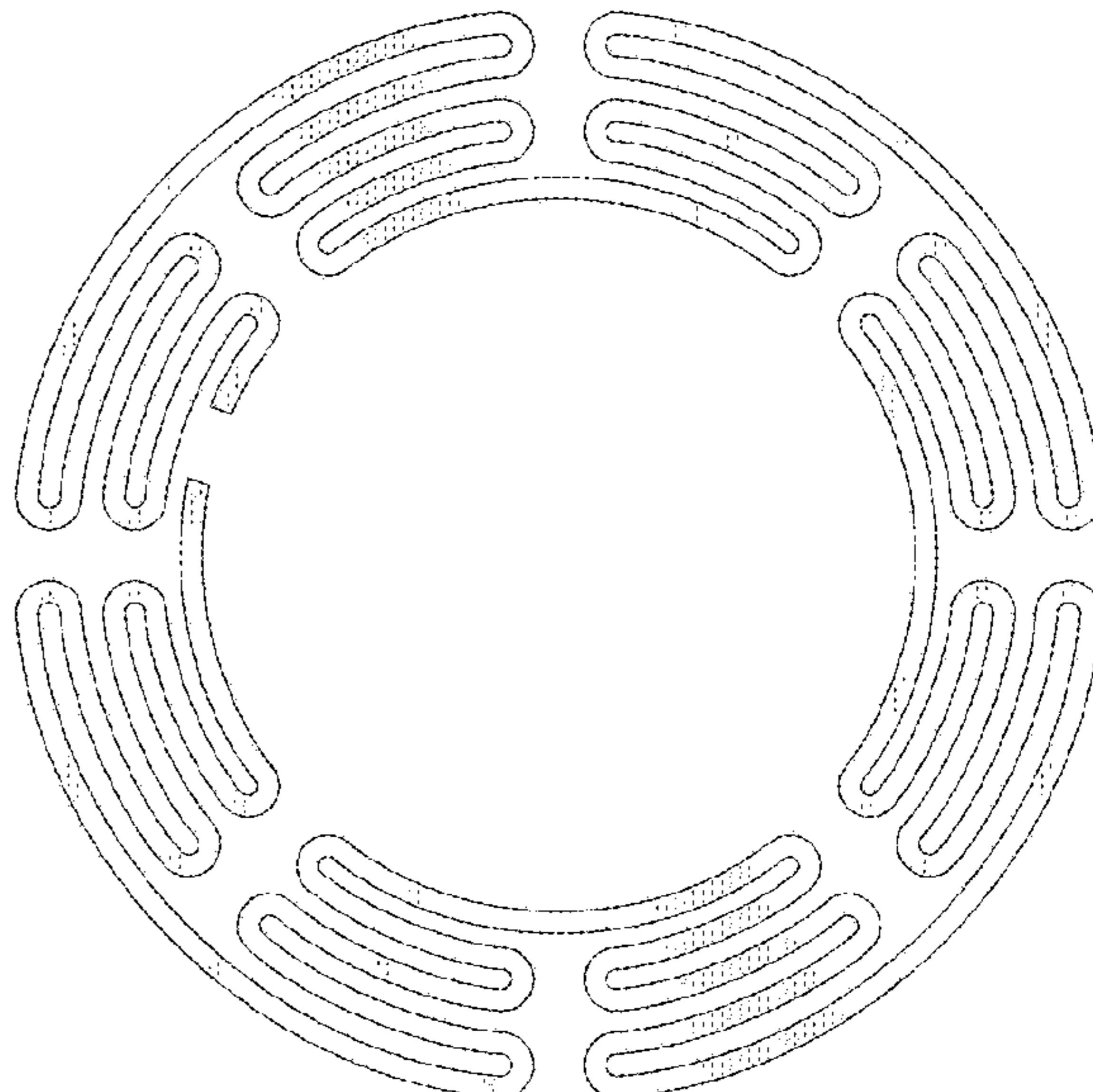
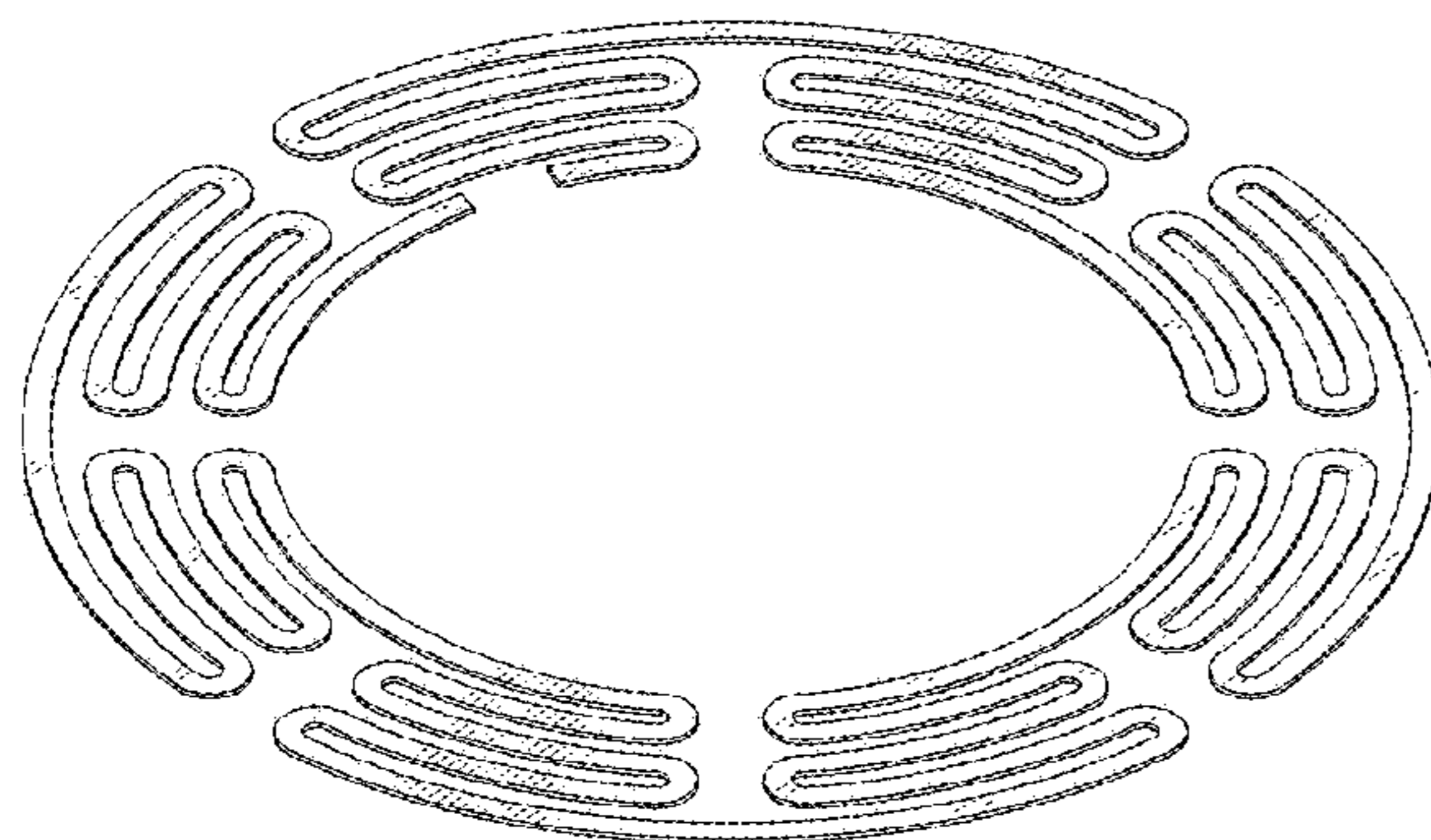
FIG. 4 is a right side elevational view thereof;

FIG. 5 is a top plan view thereof;

FIG. 6 is a bottom plan view thereof; and,

FIG. 7 is a rear elevational view.

1 Claim, 4 Drawing Sheets



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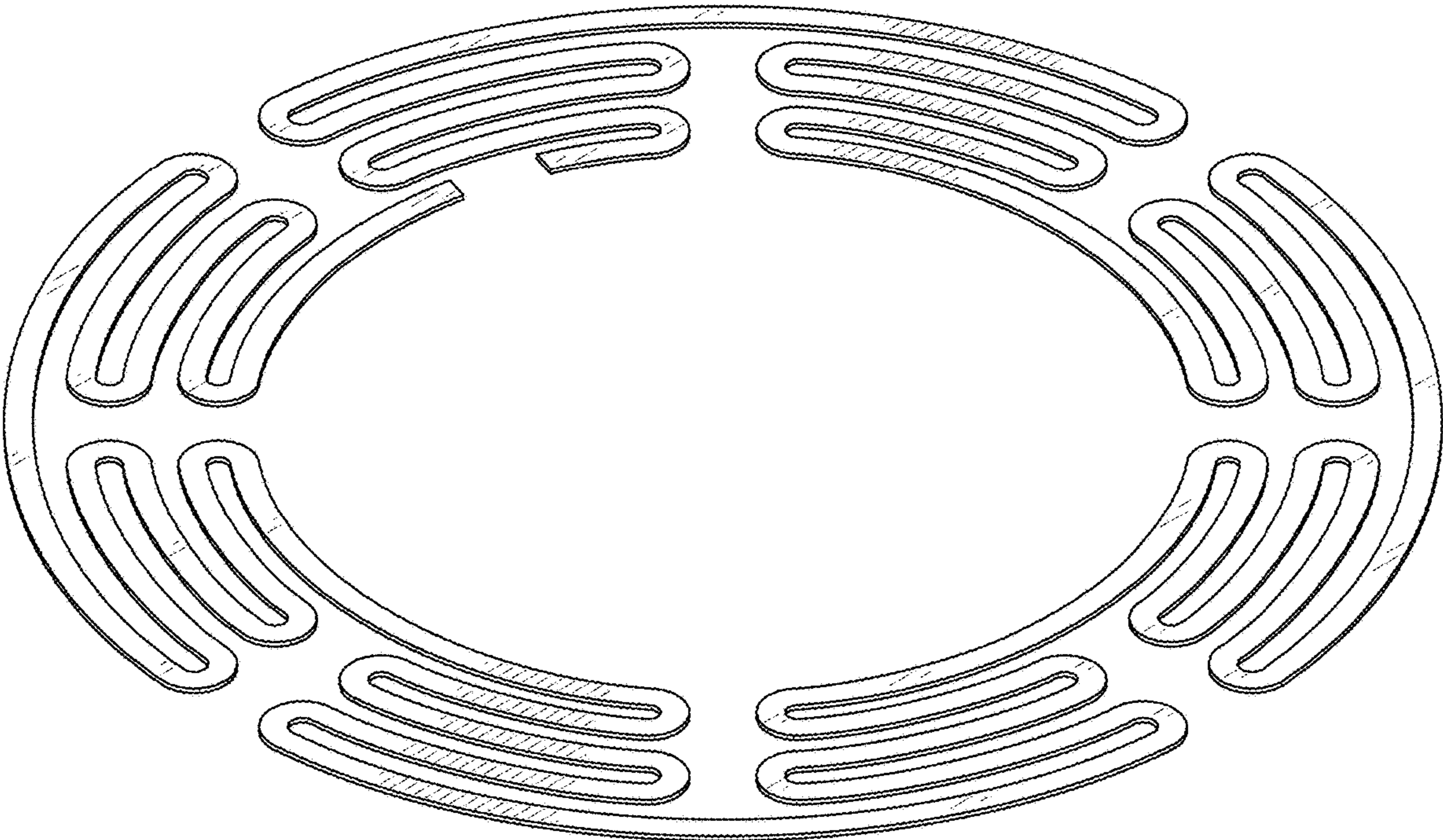


FIG. 1

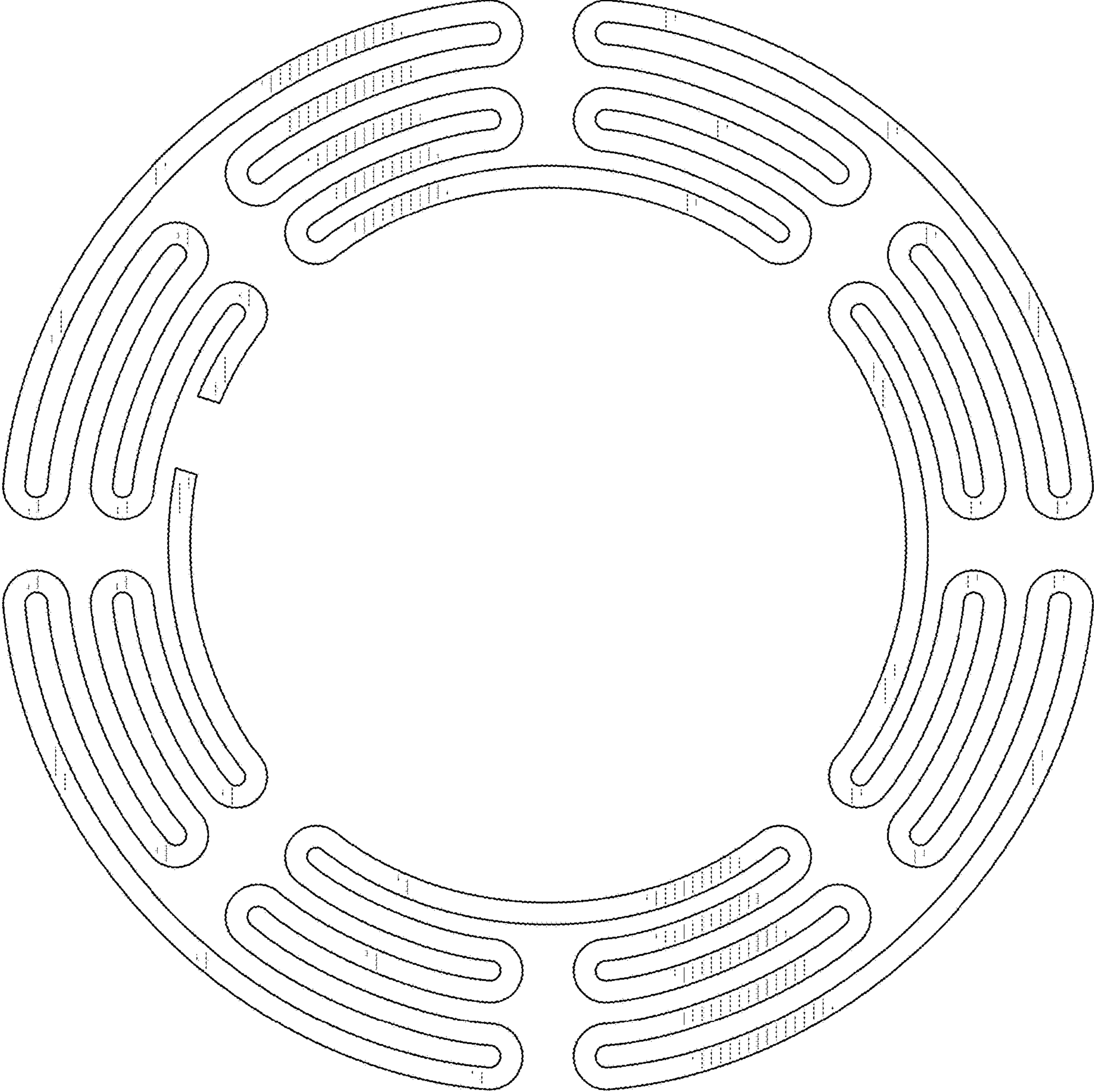


FIG. 2



FIG. 3



FIG. 4

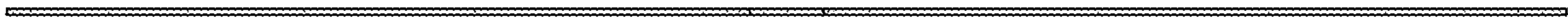


FIG. 5

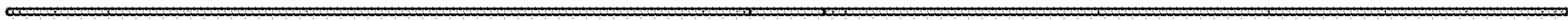


FIG. 6

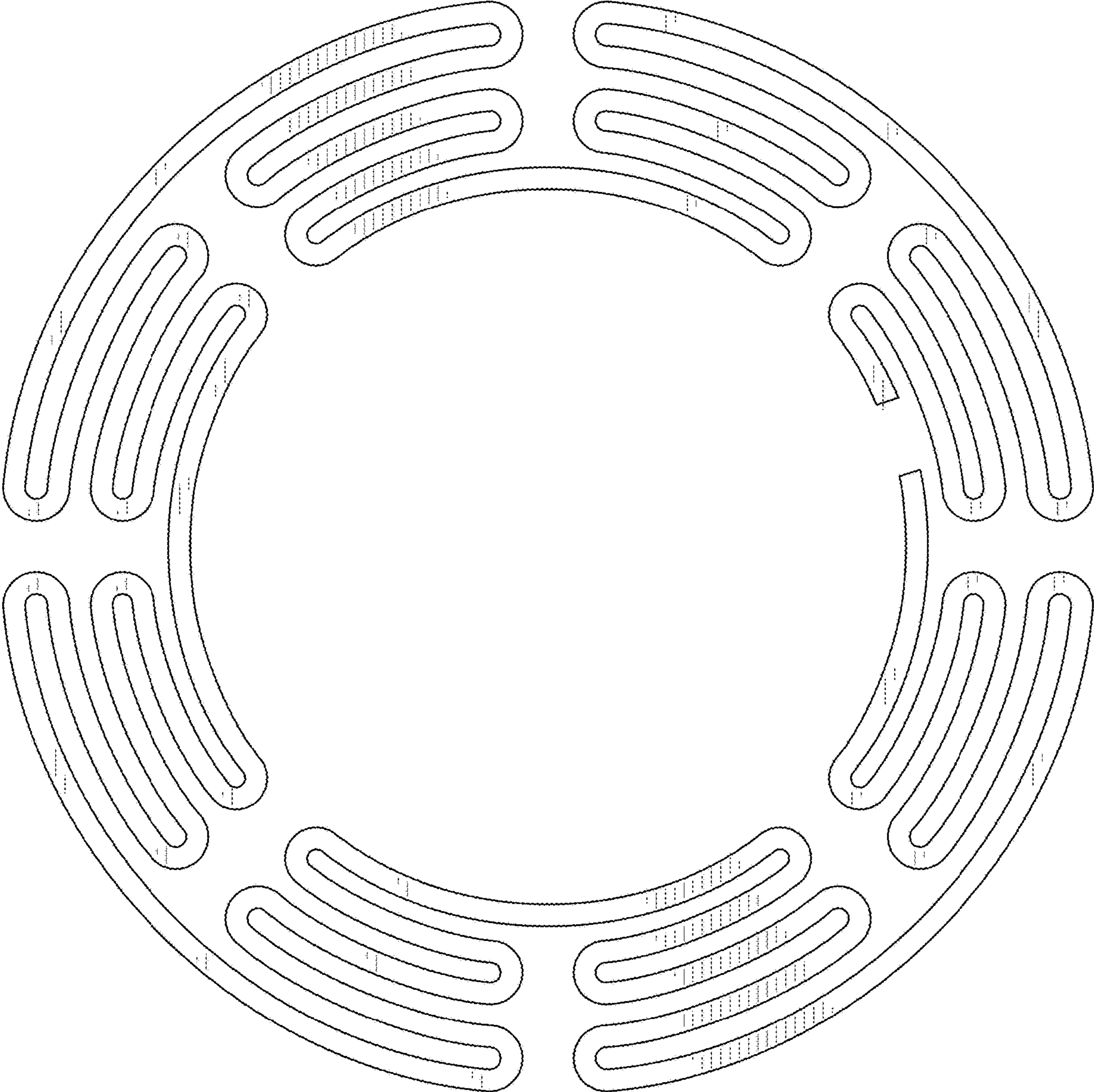


FIG. 7